Registration open for: DWL Workshop and Webinar Series





Sydney 2 Feb 2026

Scan to register for the 4th DWL Workshop, proudly sponsored by the Australian National Fabrication Facility (ANFF).

Join leading researchers, scientists, and micro/nanofabrication experts on Monday, 2 February 2026, at the University of Sydney for a one-day event exploring the latest advancements in direct write lithography (DWL)—including electron, photon, ion beam technologies, and more.



Registration also includes access to a series of educational webinars commencing in November 2025.

Want to present at the workshop?

We're calling on researchers, scientists, and experts in micro and nanofabrication to share their insights at the "Innovative Research in Direct Write Lithography Workshop." If you're working on new techniques, applications, or advancements in direct write lithography, we want to hear from you. For details on how to submit your abstract, scan the QR code on the right or <u>click here</u>.



Workshop keynote speakers

Gerald G. Lopez, Ph.D.



Director of Operations and Business & Center Associate Director Singh Center for Nanotechnology University of Pennsylvania | MAEBL Co-Founder and Board Chair | EIPBN Operations Trustee



John S. Petersen Scientific Director of Lithography, AttoLab & Å Patterning at imec & Adjunct Professor at UMD

	Melb, Syd	Adelaide	Perth	Berlin	NY	LA	Topic / Title	Facilitator / Speaker
W1	AEDT 11:00 06.11.25	ACDT 10:30 06.11.25	AWST 08:00 06.11.25	CET 1:00 06.11.25	EST 19:00 05.11.25	PST 16:00 05.11.25	50 Years of Reactive Ion Etching in Microelectronics	Christophe Vallee (University at Albany)
W2*	AEDT 16:00 27.11.25	ACDT 15:30 27.11.25	AWST 13:00 27.11.25	CET 6:00 27.11.25	EST 0:00 27.11.25	PST 21:00 26.11.25	The Physics and Chemistry of Plasma Etching (Part I)	Henri Jansen [⋆] (DTU)
W3*	AEDT 16:00 11.12.25	ACDT 15:30 11.12.25	AWST 13:00 11.12.25	CET 6:00 11.12.25	EST 0:00 11.12.25	PST 21:00 10.12.25	The Physics and Chemistry of Plasma Etching (Part II)	Henri Jansen [⋆] (DTU)
W4	AEDT 12:00 29.01.26	ACDT 11:30 29.01.26	AWST 09:00 29.01.26	CET 2:00 29.01.26	EST 20:00 28.01.26	PST 17:00 28.01.26	Atomic Mechanisms During Plasma Etching	David Graves (Princeton University)
W5	AEDT tbd .03.26	ACDT tbd .03.26	AWST tbd .03.26	CET tbd .03.26	EST tbd .03.26	PST tbd .03.26	Using the right tool for the job: Comparing ALE, RIE and IBE	Nick Chittock (Oxford Instruments Plasma Technology)
W6	AEST 11:00	ACST 10:30	AWST 9:00	CEST 3:00	EDT 21:00	PDT 18:00	Helicon Double Layer Thruster: A radiofrequency plasma source	Christine Charles (ANU)

^{*} Please be aware that the webinar you'll be watching is a pre-recorded session. After the presentation, there will be a live Q&A segment.

SCAN TO REGISTER FOR THE EVENT OR <u>CLICK HERE</u>

